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表面化学分析　俄歇电子能谱和

X 射线光电子能谱　测定峰强度的

方法和报告结果所需的信息

GB/T 28893—2012/ISO 20903:2006

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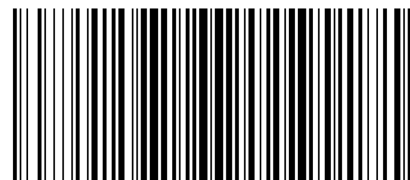

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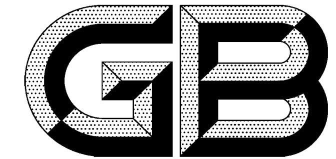

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表面化学分析　俄歇电子能谱和 X 射线光电子能谱　测定峰强度的方法和报告结果所需的信息

Surface chemical analysis—Auger electron spectroscopy and X-ray photoelectron spectroscopy—Methods used to determine peak intensities and information required when reporting results

(ISO 20903:2006,IDT)

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[32] Software can be purchased from the UK National Physical Laboratory for the calibration of the intensity scales of AES and XPS instruments. Further information is available at: http://www.

前　　言

本标准按照 GB/T 1.1—2009 给出的规则起草。

本标准使用翻译法等同采用 ISO 20903:2006《表面化学分析　俄歇电子能谱和 X 射线光电子能谱测定峰强度的方法和报告结果所需的信息》

为了方便使用，本标准做了下列编辑性修改：

——用“本标准”代替“本国际标准”。

本标准由全国微束分析标准化技术委员会(SAC/TC 38)提出并归口。

本标准负责起草单位：厦门爱劳德光电有限公司、厦门大学化学化工学院。

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